

	Hits	Search Text	DBs
50	9	((photoresist or resist) near12 (pattern or mask) near16 (inkjet near4 print\$4) near26 (fill\$4 or provide or apply\$4 or liquid or supply\$4 or coat\$4 or deposit\$4)) same (conductive or metal\$4 or electro\$4conductive or organo\$3metal\$5)) and ((inkjet or (inkjet near9 printer)) same (ink or liquid) same (fill\$4 or coat\$4 or mist\$4 or atomizer)) and (heat\$4 or anneal\$4 or bak\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
51	15	((photoresist or resist) near12 (pattern or mask)) same (inkjet near10 print\$4) near26 (fill\$4 or provide or apply\$4 or liquid or supply\$4 or coat\$4 or deposit\$4 or (shower near9 head)) same (conductive or metal\$4 or electro\$4conductive or organo\$3metal\$5)) and ((heat\$4 or anneal\$4 or bak\$4 or evaporat\$4) same (solvent or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
52	34	((photoresist or resist) near12 (pattern or mask)) same (inkjet near10 print\$4) same (discharg\$4 or provide or apply\$4 or liquid or supply\$4 or coat\$4 or deposit\$4 or (shower near9 head)) same (conductive or metal\$4 or electro\$4conductive or organo\$3metal\$5 or ink)) and ((heat\$4 or anneal\$4 or bak\$4 or evaporat\$4) same (solvent or liquid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
53	5	((photoresist or resist) near12 (pattern or mask)) same inkjet same (discharg\$4 or liquid or supply\$4 or coat\$4 or deposit\$4 or (shower near9 head)) same (conductive or metal\$4 or electro\$4conductive or organo\$3metal\$5 or ink) same fill\$4 same (opening or via or trench)) and ((heat\$4 or anneal\$4 or bak\$4 or evaporat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
54	8	((photoresist or resist) near12 (pattern or mask)) same inkjet same (discharg\$4 or liquid or supply\$4 or coat\$4 or deposit\$4 or (shower near9 head)) same (liquid or material or ink)) and (fill\$4 same (opening or via or trench) same (electroconductive or conductive or metal\$4 or organometall\$3) same (heat\$4 or anneal\$4 or bak\$4 or evaporat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
55	5	((photoresist or resist) near12 (pattern or mask)) same inkjet same (discharg\$4 or liquid or supply\$4 or coat\$4 or deposit\$4 or (shower near9 head)) same (liquid or material or ink)) and (fill\$4 same (opening or via or trench) same (pattern or mask) same (photoresist or resist) same (electroconductive or conductive or metal\$4 or organometall\$3) same (heat\$4 or anneal\$4 or bak\$4 or evaporat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB